

L Number	Hits	Search Text	DB	Time stamp
-	4	"200012465"	EPO; JPO; DERWENT	2003/11/04 10:06
-	11	"12465"	EPO; JPO; DERWENT	2003/11/03 13:00
-	0	"P200012465"	EPO; JPO; DERWENT	2003/11/03 13:01
-	2	"09237927"	EPO; JPO; DERWENT	2003/11/03 13:01
-	2	5866471.pn.	EPO; JPO; DERWENT	2003/11/04 08:28
-	1	5866471.pn.	USPAT; US-PGPUB	2003/11/04 08:28
-	30	(Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 13:52
-	19	"59015"	EPO; JPO; DERWENT; IBM_TDB	2003/11/04 10:29
-	2	"200059015"	EPO; JPO; DERWENT; IBM_TDB	2003/11/04 10:29
-	2	"200059044"	EPO; JPO; DERWENT; IBM_TDB	2003/11/04 11:08
-	1420	(427/552,553,555,558).CCLS.	USPAT; US-PGPUB	2004/04/22 15:34
-	1056	(427/226).CCLS.	USPAT; US-PGPUB	2003/11/04 11:09
-	2229	((427/248.1,255.18,255.23) or (438/503,507)).CCLS.	USPAT; US-PGPUB	2004/04/22 15:35
-	2859	(427/258,259,261,264,265,270,271).CCLS.	USPAT; US-PGPUB	2004/04/22 15:35
-	417	(423/348,349).CCLS.	USPAT; US-PGPUB	2004/04/22 15:35
-	519	(117/88,95).CCLS.	USPAT; US-PGPUB	2004/04/22 15:35
-	8126	((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.) (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.) and ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB	2004/04/23 09:14
-	14	((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.) and ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB	2004/04/22 15:37

-	3	((427/552,553,555,558).CCLS.) or ((427/258,259,261,264,265,270,271).CCLS.) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB	2004/04/22 15:39
-	32	((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) and ((427/258,259,261,264,265,270,271).CCLS.)	USPAT; US-PGPUB	2004/04/22 15:40
-	15	((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.) and ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5)) with (select\$7 or pattern\$3 or nonuniform or (non adj uniform))) and ((monolayer or (mono adj layer) or fluoroalkyl or fluorine or SAM or (self adj assembl\$3) or fluoro\$12) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5)))	USPAT; US-PGPUB	2004/04/22 15:40
-	694	((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5)) with (select\$7 or pattern\$3 or nonuniform or (non adj uniform))) and ((monolayer or (mono adj layer) or fluoroalkyl or fluorine or SAM or (self adj assembl\$3) or fluoro\$12) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5)))	USPAT; US-PGPUB	2003/11/04 11:32
-	59	((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5)) with (select\$7 or pattern\$3 or nonuniform or (non adj uniform))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5)))	USPAT; US-PGPUB	2003/11/04 12:54
-	53	((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5)) with (select\$7 or pattern\$3 or nonuniform or (non adj uniform))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5))) not (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.) and ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5)) with (select\$7 or pattern\$3 or nonuniform or (non adj uniform))) and ((monolayer or (mono adj layer) or fluoroalkyl or fluorine or SAM or (self adj assembl\$3) or fluoro\$12) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5)))	USPAT; US-PGPUB	2003/11/04 11:33

-	2	((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5)) with (select\$7 or pattern\$3 or nonuniform or (non adj uniform))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5)))	EPO; JPO; DERWENT; IBM_TDB	2003/11/04 11:39
-	7	((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$3))	EPO; JPO; DERWENT; IBM_TDB	2003/11/04 11:42
-	466	((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$3))	USPAT; US-PGPUB	2003/11/04 11:43
-	27	((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5) or pattern\$3))) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.))	USPAT; US-PGPUB	2003/11/04 11:53
-	1	((tridecafluoro near3 triethoxysilane) or FAS13 or ("FAS 13")) same (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5)	USPAT; US-PGPUB	2003/11/04 11:57
-	1	((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) same (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5)	USPAT; US-PGPUB	2003/11/04 11:57
-	60	((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5)	USPAT; US-PGPUB	2003/11/04 12:07
-	4	((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5)) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.))	USPAT; US-PGPUB	2003/11/04 11:58

-	56	((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5)) not (((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5)) and (((427/552,553,555,558).CCLS.) (427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) (427/258,259,261,264,265,270,271).CCLS.) (423/348,349).CCLS.) (117/88,95).CCLS.)))	USPAT; US-PGPUB	2003/11/04 12:01
-	0	((tridecafluoro near5 triethoxysilane) or FAS13 or ("FAS 13")) and (monolayer or (mono adj layer) or SAM or (self adj assembl\$5) or pattern or mask\$3 or inactiv\$5 or (in adj activ\$5) or (de adj activ\$5) or deactiv\$5)	EPO; JPO; DERWENT; IBM_TDB	2003/11/04 12:49
-	4	Meeks.xp,xa. and (self adj assembl\$8)	USPAT; US-PGPUB	2003/11/04 12:51
-	46692	((Si or silicon) with (coat\$3 or film or layer or deposit\$3 or \$4CVD) with (pattern\$3 or nonuniform\$3 or (non adj uniform\$3) or mask\$3))	USPAT; US-PGPUB	2003/11/04 12:59
-	573	((Si or silicon) with (coat\$3 or film or layer or deposit\$3 or \$4CVD) with (pattern\$3 or nonuniform\$3 or (non adj uniform\$3) or mask\$3))) and (((427/552,553,555,558).CCLS.) (427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) (427/258,259,261,264,265,270,271).CCLS.) (423/348,349).CCLS.) (117/88,95).CCLS.)))	USPAT; US-PGPUB	2003/11/04 12:54
-	422	((Si or silicon) with (coat\$3 or film or layer or deposit\$3 or \$4CVD) with (pattern\$3 or nonuniform\$3 or (non adj uniform\$3) or mask\$3))) and (((427/552,553,555,558).CCLS.) (427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) (427/258,259,261,264,265,270,271).CCLS.) (423/348,349).CCLS.) (117/88,95).CCLS.))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) or (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5)))	USPAT; US-PGPUB	2003/11/04 13:52
-	31013	((Si or silicon) with (coat\$3 or film or layer or deposit\$3 or \$4CVD) with (pattern\$3 or nonuniform\$3 or (non adj uniform\$3) or mask\$3))) same ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) or (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5)))	USPAT; US-PGPUB	2003/11/04 12:57
-	398	((Si or silicon) with (coat\$3 or film or layer or deposit\$3 or \$4CVD) with (pattern\$3 or nonuniform\$3 or (non adj uniform\$3) or mask\$3))) same ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) or (inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5)))	USPAT; US-PGPUB	2003/11/04 12:57

-	5	((((Si or silicon) with (coat\$3 or film or layer or deposit\$3 or \$4CVD) with (pattern\$3 or nonuniform\$3 or (non adj uniform\$3) or mask\$3))) same ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)) or (inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5)))) and ((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.))	USPAT; US-PGPUB	2003/11/04 12:57
-	13228	((Si or silicon) adj (coat\$3 or film or layer or deposit\$3 or \$4CVD) with (pattern\$3 or nonuniform\$3 or (non adj uniform\$3) or selecti\$6))	USPAT; US-PGPUB	2003/11/04 13:02
-	170	((((Si or silicon) adj (coat\$3 or film or layer or deposit\$3 or \$4CVD) with (pattern\$3 or nonuniform\$3 or (non adj uniform\$3) or selecti\$6))) and ((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.))	USPAT; US-PGPUB	2003/11/04 13:01
-	1680	((Si or silicon) adj (coat\$3 or film or layer or deposit\$3 or \$4CVD) with (pattern\$3 or nonuniform\$3 or (non adj uniform\$3) or selecti\$6) with (\$4CVD or (vapor\$9)))	USPAT; US-PGPUB	2003/11/04 13:03
-	37	((((Si or silicon) adj (coat\$3 or film or layer or deposit\$3 or \$4CVD) with (pattern\$3 or nonuniform\$3 or (non adj uniform\$3) or selecti\$6) with (\$4CVD or (vapor\$9)))) and ((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.))	USPAT; US-PGPUB	2003/11/04 13:08
-	589	(selective near2 (coat\$3 or deposit\$3 or \$4CVD) near2 (Si or silicon))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/04 13:14
-	20	((selective near2 (coat\$3 or deposit\$3 or \$4CVD) near2 (Si or silicon))) and (SAM or monolayer or (self adj assemb\$7) or (mono adj layer))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/04 13:32
-	106	(selective near2 (coat\$3 or deposit\$3 or \$4CVD) near2 (Si or silicon)) same pattern\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/04 13:30
-	103	((selective near2 (coat\$3 or deposit\$3 or \$4CVD) near2 (Si or silicon)) same pattern\$3) not (((selective near2 (coat\$3 or deposit\$3 or \$4CVD) near2 (Si or silicon))) and (SAM or monolayer or (self adj assemb\$7) or (mono adj layer)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/04 13:15
-	103	(selective near2 (coat\$3 or deposit\$3 or \$4CVD) near2 (Si or silicon))	EPO; JPO; DERWENT; IBM_TDB	2003/11/04 13:32

-	29	((selective near2 (coat\$3 or deposit\$3 or \$4CVD) near2 (Si or silicon))) and (SAM or monolayer or (self adj assemb\$7) or (mono adj layer) or inactiv\$5 or mask\$3 or deactiv\$5 or (in adj activ\$5) or (de adj activ\$5))	EPO; JPO; DERWENT; IBM_TDB	2003/11/04 13:37
-	13	(selective near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) same (SAM or monolayer or (self adj assemb\$7) or (mono adj layer))	EPO; JPO; DERWENT; IBM_TDB	2003/11/04 13:38
-	109	(selective near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) same (SAM or monolayer or (self adj assemb\$7) or (mono adj layer))	USPAT; US-PGPUB	2003/11/04 13:45
-	7	"9707429"	EPO; JPO; DERWENT	2003/11/04 13:45
-	37	((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	EPO; JPO; DERWENT; IBM_TDB	2003/11/04 13:50
-	141	((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB	2003/11/04 14:01
-	14	((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (((427/552,553,555,558).CCLS.) (427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) (427/258,259,261,264,265,270,271).CCLS.) (423/348,349).CCLS.) ((117/88,95).CCLS.))	USPAT; US-PGPUB	2003/11/04 13:52

-	127	(((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) not (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)))	USPAT; US-PGPUB	2003/11/04 13:52
-	2	(((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) not (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3)))	USPAT; US-PGPUB	2003/11/04 13:54

-	125	<p> ((((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) not (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)))) not (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) not (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)))) and ((monolayer or (mono adj layer) or SAM or (self adj assembl\$3))) </p>	USPAT; US-PGPUB	2003/11/04 13:54
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-	11	((silicon or Si) near4 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)) and (ink adj jet\$4 or inkjet\$4 or (bubble adj jet\$4) or bubblejet\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/04 14:03
-	1	((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)) same (ink adj jet\$4 or inkjet\$4 or (bubble adj jet\$4) or bubblejet\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/04 14:21
-	2	6527847.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/04 14:13
-	401	(\$4CVD or (vapor adj deposit\$3)) same ((gas or inert or nitrogen or N2 or "N.sub.2") with parallel with (crucible or source or surface or vaporizer or blow\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/04 14:29
-	28	(((\$4CVD or (vapor adj deposit\$3)) same ((gas or inert or nitrogen or N2 or "N.sub.2") with parallel with (crucible or source or surface or vaporizer or blow\$3))) and ((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/04 14:24
-	67	(\$4CVD or (vapor adj deposit\$3)) same (((inert or nonreactive or (non adj reactive) or noble) near2 gas\$4) or nitrogen or N2 or "N.sub.2" or hydrogen or H2 or "H.sub.2") with parallel with (crucible or source or surface or vaporizer or blow\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/04 14:31
-	66	(((\$4CVD or (vapor adj deposit\$3)) same (((inert or nonreactive or (non adj reactive) or noble) near2 gas\$4) or nitrogen or N2 or "N.sub.2" or hydrogen or H2 or "H.sub.2") with parallel with (crucible or source or surface or vaporizer or blow\$3))) not (((\$4CVD or (vapor adj deposit\$3)) same ((gas or inert or nitrogen or N2 or "N.sub.2") with parallel with (crucible or source or surface or vaporizer or blow\$3))) and ((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/04 14:31
-	5	6541354.pn. or 6503570.pn. or 6527847.pn. or "20030229190" or "20020034585"	USPAT; US-PGPUB	2004/04/22 13:49

-	3	6715871.pn. or 6646662.pn. or 6599582.pn.	USPAT; US-PGPUB	2004/04/22 13:50
-	39	(Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj (silane or silicon)) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 14:03
-	34	((Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj (silane or silicon)) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) not (6541354.pn. or 6503570.pn. or 6527847.pn. or "20030229190" or "20020034585")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 14:00
-	14	((Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj (silane or silicon)) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) not (6541354.pn. or 6503570.pn. or 6527847.pn. or "20030229190" or "20020034585")) and (active with inactive with \$4CVD or (vapor near2 deposit\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 14:04
-	1	((Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj (silane or silicon)) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) not (6541354.pn. or 6503570.pn. or 6527847.pn. or "20030229190" or "20020034585")) and (active with inactive with (\$4CVD or (vapor near2 deposit\$3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 14:02

-	1	((Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj (silane or silicon)) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) not (6541354.pn. or 6503570.pn. or 6527847.pn. or "20030229190" or "20020034585")) and (active with inactive)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 14:02
-	26	(Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and (((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) same (\$4CVD or (vapor near2 deposit\$3))) and ((ring adj silane) or (cyclic adj (silane or silicon)) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 14:04
-	4	(Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and (active with inactive with (\$4CVD or (vapor near2 deposit\$3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 14:07
-	3	((Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and (active with inactive with (\$4CVD or (vapor near2 deposit\$3)))) not (((Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj (silane or silicon)) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) not (6541354.pn. or 6503570.pn. or 6527847.pn. or "20030229190" or "20020034585")) and (active with inactive)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 14:05

-	2	(Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and (active with inactive with (SAM or monolayer or (mono adj layer) or monomolecular or (mono adj molecular) or (self adj assemb\$5)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 14:09
-	2	(Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((SAM or monolayer or (mono adj layer) or monomolecular or (mono adj molecular) or (self adj assemb\$5)) with (region or active or inactive or pattern\$3 or (arrang\$4 near2 liquid) or area) with (\$4CVD or (vapor near2 deposit\$3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 14:11
-	11	(Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((SAM or monolayer or (mono adj layer) or monomolecular or (mono adj molecular) or (self adj assemb\$5)) with (\$4CVD or (vapor near2 deposit\$3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 14:11
-	9	((Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((SAM or monolayer or (mono adj layer) or monomolecular or (mono adj molecular) or (self adj assemb\$5)) with (\$4CVD or (vapor near2 deposit\$3)))) not ((Furusawa.in. or Miyashita.in. or Yudasaka.in. or Shimoda.in. or Yokoyama.in. or Matsuki.in. or Takeuchi.in. or JSR.as. or (Seiko adj Epson).as.) and ((SAM or monolayer or (mono adj layer) or monomolecular or (mono adj molecular) or (self adj assemb\$5)) with (region or active or inactive or pattern\$3 or (arrang\$4 near2 liquid) or area) with (\$4CVD or (vapor near2 deposit\$3))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/22 14:11
-	1492	(427/552,553,555,558).CCLS.	USPAT; US-PGPUB	2004/04/22 15:34
-	2363	((427/248.1,255.18,255.23) or (438/503,507)).CCLS.	USPAT; US-PGPUB	2004/04/22 15:35
-	2908	(427/258,259,261,264,265,270,271).CCLS.	USPAT; US-PGPUB	2004/04/22 15:35
-	427	(423/348,349).CCLS.	USPAT; US-PGPUB	2004/04/22 15:35
-	542	(117/88,95).CCLS.	USPAT; US-PGPUB	2004/04/22 15:35
-	7427	((427/552,553,555,558).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)	USPAT; US-PGPUB USPAT; US-PGPUB	2004/04/22 15:36

-	14	((427/552,553,555,558).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)) and ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB	2004/04/22 15:43
-	3	((427/552,553,555,558).CCLS.) or ((427/258,259,261,264,265,270,271).CCLS.)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB	2004/04/22 15:39
-	34	((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) and ((427/258,259,261,264,265,270,271).CCLS.))	USPAT; US-PGPUB	2004/04/22 15:42
-	4862	((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)) and ((silicon or Si) near2 (coat\$3 or film or layer or deposit\$3 or \$4CVD or vaporiz\$5)) with (select\$7 or pattern\$3 or nonuniform or (non adj uniform))) and ((monolayer or (mono adj layer) or fluoroalkyl or fluorine or SAM or (self adj assembl\$3) or fluoro\$12) with (mask\$3 or inactiv\$5 or (in adj activ\$5) or deactiv\$5 or (de adj activ\$5))))	USPAT; US-PGPUB	2004/04/22 15:42
-	0	((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) and ((427/258,259,261,264,265,270,271).CCLS.)) and ((423/348,349).CCLS.)	USPAT; US-PGPUB	2004/04/22 15:43
-	0	((427/258,259,261,264,265,270,271).CCLS.) and ((ring adj silane) or (cyclic adj (silane or silicon)) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB	2004/04/22 15:44

-	14	((427/552,553,555,558).CCLS.) or ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) or ((117/88,95).CCLS.)) and ((ring adj silane) or (cyclic adj (silane or silicon)) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB	2004/04/22 15:59
-	34	((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) and (427/258,259,261,264,265,270,271).CCLS.)	USPAT; US-PGPUB	2004/04/22 15:46
-	123	((427/552,553,555,558).CCLS.) ((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) (427/258,259,261,264,265,270,271).CCLS.) (423/348,349).CCLS.) ((117/88,95).CCLS.)) and ((\$4CVD or (vapor near2 deposit\$3) or vaporiz\$4) same ((pattern\$3 or active or inactive or region) near6 (liquid or source or reagent or solution)))	USPAT; US-PGPUB	2004/04/22 15:48
-	7	((ring adj silane) or (cyclic adj (silane or silicon)) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)) same (pattern\$3 or selectiv\$5)	USPAT; US-PGPUB	2004/04/22 16:05
-	30	((ring adj silane) or (cyclic adj (silane or silicon)) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)) same (vapor\$9 or \$4CVD)	USPAT; US-PGPUB	2004/04/22 16:04
-	9	((ring adj silane) or (cyclic adj (silane or silicon)) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)) same (SAM or monolayer or monomolecular or (mono adj (layer or molecular)) or (self adj assemb\$5) or mask\$3 or photomask\$3)	USPAT; US-PGPUB	2004/04/23 08:31
-	103	((ring adj silane) or (cyclic adj (silane or silicon)) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)) same (pattern\$3 or select\$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 08:32

-	26	((ring adj silane) or (cyclic adj (silane or silicon)) or cyclosilane or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)) same ((pattern\$3 or select\$5) with (coat\$3 or film or layer or deposit\$4 or \$4CVD or apply\$4)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 08:36
-	37	((vapor near2 deposit\$3) or \$4CVD) near3 (selecti\$6 or pattern\$5 or nonuniform\$4 or (non adj uniform\$5))) and ((evaporat\$5 or vaporiz\$5) near3 (liquid or reagent or solution or source or crucible or material) near3 (pattern or select\$7))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 08:45
-	38549	((vapor near2 deposit\$3) or \$4CVD or coat\$3 or apply\$3 or deposit\$4 or film or layer) near3 (selecti\$6 or pattern\$5 or nonuniform\$4 or (non adj uniform\$5))) and ((liquid or reagent or solution or source or crucible or material) with (pattern or select\$7 or region) with (mask\$3 or monolayer or SAM or (self adj assemb\$5) or (mono adj layer) or monomolecular or (mono adj molecular)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 08:48
-	690	((vapor near2 deposit\$3) or \$4CVD or coat\$3 or apply\$3 or deposit\$4 or film or layer) near3 (selecti\$6 or pattern\$5 or nonuniform\$4 or (non adj uniform\$5))) and ((liquid or reagent or solution or source or crucible or material) with (pattern or select\$7 or region) with (monolayer or SAM or (self adj assemb\$5) or (mono adj layer) or monomolecular or (mono adj molecular)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 08:50
-	463	((vapor near2 deposit\$3) or \$4CVD or coat\$3 or apply\$3 or deposit\$4 or film or layer) near3 (selecti\$6 or pattern\$5 or nonuniform\$4 or (non adj uniform\$5))) and ((liquid or reagent or solution or source or crucible or material) with (pattern or select\$7 or region) with (monolayer or SAM or (self adj assemb\$5) or (mono adj layer) or monomolecular or (mono adj molecular))) and (evaporat\$5 or vaporiz\$5 or \$4CVD or (vapor adj deposit\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 08:53
-	74	((vapor near2 deposit\$3) or \$4CVD or coat\$3 or apply\$3 or deposit\$4 or film or layer) near3 (selecti\$6 or pattern\$5 or nonuniform\$4 or (non adj uniform\$5))) and ((liquid or reagent or solution or source or crucible or material) with (pattern or select\$7 or region) with (monolayer or SAM or (self adj assemb\$5) or (mono adj layer) or monomolecular or (mono adj molecular)) with (mask\$3 or activ\$5 or inactiv\$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 08:50
-	17	((vapor near2 deposit\$3) or \$4CVD or coat\$3 or apply\$3 or deposit\$4 or film or layer) near3 (selecti\$6 or pattern\$5 or nonuniform\$4 or (non adj uniform\$5))) and ((liquid or reagent or solution or source or crucible or material) with (pattern or select\$7 or region) with (monolayer or SAM or (self adj assemb\$5) or (mono adj layer) or monomolecular or (mono adj molecular)) with (mask\$3 or activ\$5 or inactiv\$5)) and ((evaporat\$5 or vaporiz\$5 or \$4CVD or (vapor adj deposit\$3)) with (selectiv\$5 or pattern\$4 or region or portion))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 08:58

-	883	(\$4CVD or vaporiz\$5 or evaporat\$5 or (vapor adj deposit\$3)) near3 (crucible or source or surface) near3 (pattern\$3 or (active near3 inactive))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 09:00
-	123	(\$4CVD or vaporiz\$5 or evaporat\$5 or (vapor adj deposit\$3)) near3 (crucible or source) near3 (pattern\$3 or (active near3 inactive))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 09:09
-	6	(((\$4CVD or coat\$3 or film or layer or deposit\$3) near3 (selectiv\$4 or pattern\$3)) and ((liquid or solution or reagent) near6 (surface or substrate) near6 (active near4 inactive))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 09:12
-	615	(((\$4CVD or coat\$3 or film or layer or deposit\$3) near3 (selectiv\$4 or pattern\$3)) and ((liquid or solution or reagent) near6 (surface or substrate) near6 (pattern\$3 or select\$7)) same (\$4CVD or vapor\$9 or evaporat\$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 09:13
-	9407	((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.))	USPAT; US-PGPUB	2004/04/23 09:14
-	39	(((\$4CVD or coat\$3 or film or layer or deposit\$3) near3 (selectiv\$4 or pattern\$3)) and ((liquid or solution or reagent) near6 (surface or substrate) near6 (pattern\$3 or select\$7)) same (\$4CVD or vapor\$9 or evaporat\$5))) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)))	USPAT; US-PGPUB	2004/04/23 09:19
-	22	(((vapor near2 deposit\$3) or \$4CVD or coat\$3 or apply\$3 or deposit\$4 or film or layer) near3 (selecti\$6 or pattern\$5 or nonuniform\$4 or (non adj uniform\$5))) and ((liquid or reagent or solution or source or crucible or material) with (pattern or select\$7 or region) with (monolayer or SAM or (self adj assemb\$5) or (mono adj layer) or monomolecular or (mono adj molecular)))) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)))	USPAT; US-PGPUB	2004/04/23 09:20
-	56	((vapor adj deposit\$3) or \$4CVD) near2 (crucible or source or liquid or solution) near2 (selectiv\$5 or pattern\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 09:23
-	81	((vapor adj deposit\$3) or \$4CVD) near3 (crucible or source or liquid or solution) near3 (mask\$3 or SAM or monolayer or monomolecular or (mono adj (layer or molecular)) or (self adj assembl\$4)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 09:27

-	11	((vapor adj deposit\$3) or \$4CVD) near3 (selectiv\$5 or pattern\$3)) and ((mask\$3 or inactiv\$5) near4 (SAM or monolayer or monomolecular or (mono adj (layer or molecular)) or (self adj assembl\$4)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 09:30
-	18	((vapor adj deposit\$3) or \$4CVD or coat\$3 or film or deposit\$3 or layer or apply\$3) near3 (selectiv\$5 or pattern\$3)) and ((inactiv\$5) with (activ\$5) with (\$4CVD or (vapor near2 deposit\$4)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 09:33
-	40	((liquid or solution) near2 (vaporiz\$5 or evaporat\$4) near2 pattern\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 09:34
-	2	((liquid or solution) near2 (vaporiz\$5 or evaporat\$4) near2 pattern\$3) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 09:33
-	90	((liquid or solution) near3 (vaporiz\$5 or evaporat\$4) near3 pattern\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 09:34
-	2	((liquid or solution) near3 (vaporiz\$5 or evaporat\$4) near3 pattern\$3) and (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 09:34
-	88	((liquid or solution) near3 (vaporiz\$5 or evaporat\$4) near3 pattern\$3) not (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) (((427/248.1,255.18,255.23) or (438/503,507)).CCLS.) ((427/258,259,261,264,265,270,271).CCLS.) ((423/348,349).CCLS.) ((117/88,95).CCLS.)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/04/23 10:26